

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Previously Presented): A method for determining a substrate type comprising:

- disposing said substrate in a plasma processing system;
- exposing said substrate to a plasma process in said plasma processing system;
- detecting an optical signal resulting from an optical emission spectrum of said plasma process performed on said substrate, said optical signal including an intensity ratio of a first intensity corresponding to a first wavelength band to a second intensity corresponding to a second wavelength band; and
- determining whether said substrate type is a correct substrate type or an incorrect substrate type by comparing said optical signal with a threshold value,
- said threshold value comprises setting said threshold value to an average of an intensity ratio corresponding to the incorrect substrate type and an intensity ratio corresponding to the correct substrate type.

Claim 2 (Original): The method of claim 1, wherein said exposing said substrate to said process comprises exposing said substrate to a seasoning process.

Claim 3 (Original): The method of claim 1, wherein said detecting said optical signal comprises using optical emission spectroscopy (OES).

Claim 4-6 (Canceled).

Claim 7 (Previously Presented): The method of claim 1, wherein said determining said substrate type comprises determining the correct substrate type when said intensity ratio has a value less than said threshold value, and determining the incorrect substrate type when said intensity ratio has a value greater than said threshold value.

Claim 8 (Previously Presented): The method of claim 1, wherein said determining said substrate type comprises identifying a seasoning substrate when said intensity ratio has a value less than said threshold value, and identifying a bare silicon substrate when said intensity ratio has a value greater than said threshold value.

Claim 9 (Canceled).

Claim 10 (Previously Presented): The method of claim 1, wherein said comparing said optical signal with said threshold value comprises comparing said optical signal with at least one of a static threshold value, or a dynamic threshold value.

Claim 11-20 (Canceled).

Claim 21 (Previously Presented): A method for determining a substrate type comprising:

- disposing said substrate in a plasma processing system;
- exposing said substrate to a seasoning process in said plasma processing system;
- detecting an optical signal resulting from an optical emission spectrum of said process using optical emission spectroscopy, wherein said optical signal comprises an intensity ratio

of a first intensity corresponding to a first wavelength band to a second intensity corresponding to a second wavelength band; and

determining whether said substrate is a correct substrate type or an incorrect substrate type by comparing said optical signal with a threshold value, wherein said threshold value is set to an average value between an intensity ratio for the correct substrate type and an intensity ratio for the incorrect substrate type.

Claim 22 (Original): The method of claim 1, wherein said exposing said substrate to said process comprises exposing said substrate to a production process.